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Isotopic study of Raman active phonon modes in  $\beta$  – Ga<sub>2</sub>O<sub>3</sub>

# Supplementary Material: Isotopic study of Raman active phonon modes in $\beta$ – Ga<sub>2</sub>O<sub>3</sub>

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# **AFM MICROGRAPHS**

AFM micrographs evidence a morphology characterized by (i) the presence of deep trenches, almost orthogonal to the [001] in-plane direction, related to island-coalesence growth mechanism (Fig. S1a), [1] and (ii) (110) facets visible as elongated features oriented along the [001] orientation as a result of the metal-rich growth conditions of the layer (Fig. S1b).



FIGURE S1. (a) 5x5 and (b) 1x1  $\mu$ m AFM images of the 1.6  $\mu$ m thick (010)  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> homoepitaxial layer deposited with <sup>18</sup>O isotopes.

### **TOF-SIMS MEASUREMENTS**

Fig. S2 illustrates the ToF-SIMS depth profiles for the isotope fraction of <sup>18</sup>O. The <sup>18</sup>O isotope fraction  $n^*$  is calculated by the SIMS intensities:

$$n^* = \frac{I({}^{18}\mathrm{O}^-)}{I({}^{16}\mathrm{O}^-) + I({}^{18}\mathrm{O}^-)}$$
(S1)

In the film, 96.3% <sup>18</sup>O are employed (nominal isotope fraction of the gas: 97.39%). At the interface, the isotope fraction is decreased over a transient region with an extent of 300 nm to 0.3%, which is slightly above the natural isotope abundance of 0.2%.



**FIGURE S2.** ToF-SIMS analysis of the thin film. <sup>18</sup>O isotope fraction analyzed with 25 keV Ga<sup>+</sup> analysis beam and 2 kV Cs<sup>+</sup> sputter beam. The interface (1650 nm) is obtained from the depth of 50% of the film's maximum isotope fraction. The inset shows the same graph with linear scale.

#### SCHEME OF RAMAN-ACTIVE PHONON MODES

For the monoclinic crystal structure of  $\beta$ -Ga<sub>2</sub>O<sub>3</sub> there are 15 Raman-active phonon modes (10 with  $A_g$  and 5 with  $B_g$  symmetry), the schemes of which are illustrated in Fig. S3.  $A_g$ -modes are presented in projection on the b-plane. Arrows indicate the displacements of the corresponding atoms, with the length of the arrows representing each atom's



**FIGURE S3.** Scheme of Raman-active modes within the primitive unit cell of  $\beta$ -Ga<sub>2</sub>O<sub>3</sub>.  $A_g$ -modes are shown in projection on the *b*-plane. The ( $\overline{2}01$ ) plane (blue) is indicated for the illustration of  $B_g$ -modes. Arrows indicate the displacements of basis atoms, with lengths denoting the amplitude of vibration. Different red and grey colours indicate individual O and Ga lattice site atoms.

amplitude of vibration.  $A_g$ -modes are seen to oscillate within the b-plane, whereas modes of  $B_g$ -symmetry vibrate perpendicular to the same.

# REFERENCES

1. P. Mazzolini and O. Bierwagen, "Towards smooth (010)  $\beta$  – Ga<sub>2</sub>O<sub>3</sub> films homoepitaxially grown by plasma assisted molecular beam epitaxy: The impact of substrate offcut and metal-to-oxygen flux ratio," J. Phys. D. Appl. Phys. **53**, 354003 (2020).